

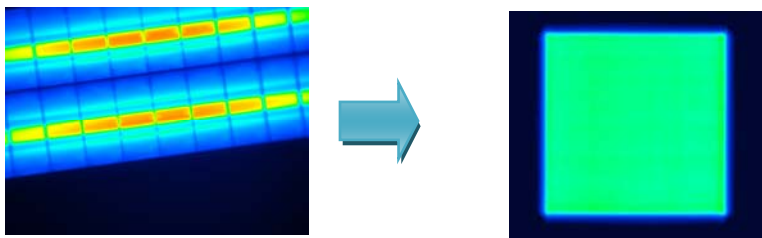
## Large Field Illumination Solutions

### Improve The Light Uniformity of Your Illumination System (DUV to IR)

The performance of large field exposure or inspection systems is often limited by the poor uniformity of the illumination light.

## Don't accept poor light uniformity and low efficiency!

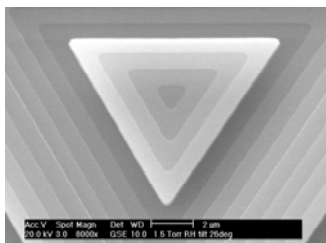
SUSS MicroOptics provides illumination solutions for almost any application requiring an illuminated area from 100  $\mu\text{m}^2$  to 1  $\text{m}^2$ . Our high-quality Fused Silica shows excellent transmission at any wavelength from 190 nm to 5  $\mu\text{m}$  wavelength.



*SUSS Mask Aligner MA200 Compact*

### Supplier for Major Equipment Manufacturers

SUSS MicroOptics is "Preferred Supplier" for major equipment suppliers like Carl Zeiss SMT AG (ASML DUV Stepper, TCZ Laser Annealing) and receives highest rankings in customer satisfaction. SUSS



*16-level DOE for Excimer*

MicroOptics key scientist have more than 20 years experience in micro-optics and optical system design. Our wafer-based manufacturing technology (8") enables us to provide outstanding quality for very competitive prices.

### MO Exposure Optics for SUSS MicroTec Mask Aligner

SUSS MicroOptics has recently developed a novel illumination systems for all SUSS MicroTec Mask Aligners, the MO Exposure Optics. The new optical system is based on unique microlens arrays of high optical quality to provide higher intensity, improved exposure light uniformity and customized illumination shaping. This allows users of SUSS MicroTec mask aligners to optimize their process window and enhance yield in contact and proximity lithography.

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